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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/891,905	06/26/2001	Gwan-Byeob Koh	5649-873	1424

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EXAMINER
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GEBREMARIAM, SAMUEL A

ART UNIT	PAPER NUMBER
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2811

DATE MAILED: 10/23/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

<b>Office Action Summary</b>	Application No.	Applicant(s)
	09/891,905	KOH ET AL.
	Examiner	Art Unit
	Samuel A Gebremariam	2811

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --  
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM  
THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

1) Responsive to communication(s) filed on 15 July 2002.  
 2a) This action is FINAL.                            2b) This action is non-final.  
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

4) Claim(s) 1-3 and 17-23 is/are pending in the application.  
 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.  
 5) Claim(s) \_\_\_\_\_ is/are allowed.  
 6) Claim(s) 1-3 and 17-23 is/are rejected.  
 7) Claim(s) \_\_\_\_\_ is/are objected to.  
 8) Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

9) The specification is objected to by the Examiner.  
 10) The drawing(s) filed on \_\_\_\_\_ is/are: a) accepted or b) objected to by the Examiner.  
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
 11) The proposed drawing correction filed on \_\_\_\_\_ is: a) approved b) disapproved by the Examiner.  
 If approved, corrected drawings are required in reply to this Office action.  
 12) The oath or declaration is objected to by the Examiner.

**Priority under 35 U.S.C. §§ 119 and 120**

13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  
 a) All b) Some \* c) None of:  
 1. Certified copies of the priority documents have been received.  
 2. Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.  
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).  
 \* See the attached detailed Office action for a list of the certified copies not received.  
 14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).  
 a) The translation of the foreign language provisional application has been received.  
 15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

**Attachment(s)**

1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892)	4) <input type="checkbox"/> Interview Summary (PTO-413) Paper No(s). _____ .
2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)	5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152)
3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____ .	6) <input type="checkbox"/> Other: _____ .

**DETAILED ACTION*****Claim Rejections - 35 USC § 102***

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-3, 17, 18 and 20-23 are rejected under 35 U.S.C. 102(b) as being anticipated by Nara JP patent No. 410056147A.

Regarding claim 1, Nara teaches (fig. A-E) a method of forming a channel region between isolation regions of an integrated circuit substrate, the method comprising; forming a mask (5) on the isolation region (2) that extends onto a portion of the substrate adjacent to the isolation region to provide a shielded portion of the substrate adjacent to the isolation region and an exposed portion of the substrate spaced apart from the isolation region having the shielded portion in between and forming a channel region (6) in the exposed portion of the substrate; forming a plurality of gate (4) electrodes on the channel region and implanting ions using the plurality of gate electrodes as an implant mask to form source/drain regions (7) associated with the plurality of the gate electrodes and to define a separate channel regions from the channel region that are self-aligned to the plurality of the gate electrodes.

Regarding claim 3, Nara teaches the entire claimed process of claim 1 above including implanting boron ions in the exposed region (fig. 1C)

Regarding claim 17, Nara teaches the entire claimed process of claim 1 above including at least one of the source/drain regions is in the exposed portion (fig. 1E).

Regarding claim 18, Nara teaches the entire claimed process of claim 1 above including implanting first ions (fig. 1C) of first conductive type and implanting second ions of second conductive type (fig. 1D).

Regions (10) and (18) are formed using boron ions which is a p-type impurity and source/drain region is formed using an n-type dopant. Therefore the dopants are inherently first and second conductive type.

Regarding claim 20, Nara teaches the entire claimed process of claim 1 above including the source/drain regions comprise lightly doped source/drain structures (7) (fig. 1D).

Regarding claim 21, Nara teaches a method of forming a channel region between isolation regions of an integrated circuit substrate, the method comprising: forming a mask (5) on first and second adjacent isolation regions (2) in an integrated circuit substrate (1) and extending onto an active area between the first and second isolation regions to define first and second shielded portions (fig. B) adjacent to the first and second isolation regions and an exposed portion of the substrate; forming a single channel region (6) (fig. C) in the exposed portion of the substrate; forming a plurality of gate electrodes (4) on the single channel region and implanting ions using a plurality of the gate electrodes as an implant mask to form source/drain regions (7) associated with the plurality of the gate electrodes and to form first and second spaced apart channel regions from the single channel region (6) (figs. A-E).

Regarding claim 22, Nara teaches the entire claimed process of claim 1 above including implanting ions comprises implanting ions to form the first and second spaced apart channel regions self-aligned to the plurality of the gate electrodes (figs. C-D).

Regarding claim 23, Nara teaches the entire claimed process of claim 1 above including forming a single channel region (6) comprises implanting boron ions in the exposed portion (page 2, translation drawing C).

***Claim Rejections - 35 USC § 103***

2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claim 19, is rejected under 35 U.S.C. 103(a) as being unpatentable over Nara.

Nara teaches substantially the entire claimed process of claim 1 above except explicitly stating that the implant step of claim 18 comprises implanting boron ions to provide a first concentration of about  $1 \times 10^{17}$  ions/cm<sup>3</sup>.

The implant concentration is a variable that is subject to optimization through routine experimentation. It would have been obvious to one of ordinary skill to in the art at the time the invention was made to vary the implant concentration, since it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art. *In re Boesch*, 617 F.2d 272, 205 USPQ 215 (CCPA 1980).

Claim 2, is rejected under 35 U.S.C. 103(a) as being unpatentable over Nara in view of Odake US patent No. 6,165,825.

Regarding claim 2, Nara teaches substantially the entire claimed process of claim 1 above including forming the channel region comprises; implanting a first concentration of ions (fig. 1C) in the shielded region adjacent to the isolation region and wherein implanting ions comprises implanting a second concentration of ions in the channel region spaced apart from the isolation region.

Nara fails to teach the second concentration is greater than the first concentration.

Odake teaches forming channel region by first implanting first concentration of ions (10) in the shield region and implanting second concentration of ions in the channel region where the second concentration is greater than the first (fig. 5a-5f and column 12, lines 60-67 and col. 13, lines 1-12).

Furthermore parameters such as implant concentration in the art of semiconductor manufacturing process are subject to routine experimentation and optimization to achieve the desired device characteristics during device fabrication.

It would have been obvious to one of ordinary skill in the art at the time the invention was made to incorporate the implant steps taught by Odake in the process of Nara in order to form a MOSFET with better threshold control.

### ***Response to Arguments***

3. Applicant's arguments with respect to claims 1-3 and 17-23 have been considered but are moot in view of the new ground(s) of rejection.

***Conclusion***

4. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Reference A cited as being related to fabrication of DRAM.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Samuel Admassu Gebremariam whose telephone number is 703 305 1913. The examiner can normally be reached on 8:00am-4:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (703) 305-7646. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 308-7722 for regular communications and (703) 308-7724 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Samuel Admassu Gebremariam  
October 16, 2002

*Tom Thomas*  
TOM THOMAS  
SUPERVISORY PATENT EXAMINER  
TECHNOLOGY CENTER 2800